

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Kei WATANABE, et al.) *Parent* Group Art Unit: 2812
)
Div. of Application No.: 10/201,892 filed) *Parent* Examiner: Nguyen, Ha T.
July 25, 2002)
)
Filed: Herewith)
)
For: SEMICONDUCTOR DEVICE AND)
MANUFACTURING METHOD)
THEREOF)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), Applicants bring to the attention of the Examiner the documents listed on the attached PTO-1449. Applicants file this Information Disclosure Statement together with the above-referenced divisional application.

Applicants previously submitted copies of the listed documents, or they were cited by the Examiner in prior application No. 10/201,892, filing date July 25, 2002, upon which Applicants rely for the benefits provided in 35 U.S.C. § 120. Applicants respectfully request that the Examiner consider the listed documents, and indicate that they were considered by making appropriate notations on the attached form.

The following is a concise statement of relevance of each of the non-English language documents:

1. Japanese Patent Application Publication No. 3234121 - discloses a SiOF film which has characteristic network structure.
2. Japanese Patent Application Publication No. 6-302704 - discloses a similar wiring structure to that of the above-identified document JP 3234121, (see Figure 3).

This submission does not represent that a search has been made or that no better art exists, and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and Applicants determine that the cited documents do not constitute "prior art" under United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such documents.

Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: September 24, 2003

By: 

David M. Longo
Reg. No. 53,235

FINNEGAN
HENDERSON
FARABOW
GARRETT &
DUNNER LLP

1300 I Street, NW
Washington, DC 20005
202.408.4000
Fax 202.408.4400
www.finnegan.com

INFORMATION DISCLOSURE CITATION

Atty. Docket No.	04329.2858-01	Div. of Serial No.	10/201,892
Applicant	Kei WATANABE, et al.		
Filing Date	Herewith	Prior Group:	2812

U.S. PATENT DOCUMENTS						
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
	6,008,120	12/1999	Lee			
	5,429,995	07/1995	Nishiyama et al.			
	6,057,251	05/2000	Goo et al.			
	6,255,233	07/2001	Smith et al.			
	6,429,105	08/2002	Kunikiyo			
	6,437,424	08/2002	Noma et al.			

FOREIGN PATENT DOCUMENTS						
	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
	6-302704	10/1994	Japan			No
	3234121	09/2001	Japan			No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
	Richard Swope, et al., "Improvement of Adhesion Properties of Fluorinated Silica Glass Films by Nitrous Oxide Plasma Treatment," Journal of the Electrochemical Society, Vol. 144, No. 7, July 1997, pp. 2559-2564
	Kwon et al., "Semiconductor Device Having Improved Metal Line Structure and Manufacturing Method Therefor," U.S. Application Publication No. 2001/0006255 A1, published July 5, 2001

Examiner	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	
Form PTO 1449	Patent and Trademark Office - U.S. Department of Commerce